

ABSTRACT

A method for manufacturing a Co-base sintered alloy sputtering target for the formation of a magnetic recording film which is less likely to generate particles, characterized by including providing, as raw material powders, a Cr-Co alloy powder consisting of 50 to 70 atomic% of Cr and a remainder containing Co, a Pt powder, a nonmagnetic oxide powder, and a Co powder, blending and mixing the raw material powders together so as to give a chemical composition consisting of 2 to 15 mol% of a non-magnetic oxide, 3 to 20 mol% of Cr, and 5 to 30 mol% of Pt and a remainder containing Co, and sintering the mixture under pressure; a method for manufacturing a Co-base sintered alloy sputtering target for the formation of a magnetic recording film which is less likely to generate particles, including providing, as raw materials, a Pt-Cr binary alloy powder consisting of 10 to 90 atomic % of Pt and a remainder containing Cr, a Pt powder, a non-magnetic oxide powder, and a Co powder, blending and mixing the raw material powders so as to give a chemical composition of 2 to 15 mol% of a nonmagnetic oxide, 3 to 20 mol% of Cr, and 5 to 30 mol% of Pt and a remainder containing Co, and then sintering the mixture under pressure; and a Co-base sintered alloy sputtering target for the formation of a magnetic recording film, characterized by having a chemical composition consisting of 2 to 15 mol% of a nonmagnetic oxide, 3 to 20 mol% of Cr, and 5 to 30 mol% of Pt and a remainder containing Co and inevitable impurities, and in which the number of chromium oxide aggregates having an absolute maximum length of more than 5 μm in the microstructure is not more than 500 aggregates/ mm^2 .